

ABSTRACT OF THE DISCLOSURE

In one illustrative embodiment, a method is provided that controls a stepper to position a focal plane of a light source adjacent a top surface of a layer of photoresist. A metrology tool is used to measure a thickness of the layer of photoresist, and a controller uses the thickness measurement to determine a position of the top surface of the layer of photoresist. The controller delivers a control signal to the stepper, causing the stepper to move the focal plane of the light source adjacent the top surface of the layer of photoresist.

09851900.050901  
106050" 006T5860